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APPLICATION NO.	F	ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/040,017 01/04/2002		01/04/2002	. Mischa Megens	1-10-5	8821
47394	7590	10/20/2006		EXAM	INER
HITT GAIN	•		ANGEBRANNI	OT, MARTIN J	
PO BOX 832570			ART UNIT	PAPER NUMBER	
RICHARDSON, TX 75083			1756		

DATE MAILED: 10/20/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)			
		10/040,017	MEGENS ET AL.			
	Office Action Summary	Examiner	Art Unit			
•		Martin J. Angebranndt	1756			
 Period for		nication appears on the cover sheet with	the correspondence address			
WHICH - Extension after SIX - If NO pe - Failure to Any repl	EVER IS LONGER, FROM THE Nons of time may be available under the provision (6) MONTHS from the mailing date of this comeriod for reply is specified above, the maximum storeply within the set or extended period for reply	MAILING DATE OF THIS COMMUNICA s of 37 CFR 1.136(a). In no event, however, may a rep munication. statutory period will apply and will expire SIX (6) MONTH by will, by statute, cause the application to become ABAI after the mailing date of this communication, even if time	ATION. bly be timely filed  HS from the mailing date of this communication. NDONED (35 U.S.C. § 133).			
Status						
1)⊠ R	esponsive to communication(s) fil	ed on 15 August 2006.				
·	his action is <b>FINAL</b> .	2b) This action is non-final.				
	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
cl	osed in accordance with the pract	tice under <i>Ex parte Quayle</i> , 1935 C.D.	11, 453 O.G. 213.			
Disposition	n of Claims		•			
4)⊠ C	laim(s) <u>1-10,14-20,22,23 and 26-2</u>	29 is/are pending in the application.				
	· · · · · · · · · · · · · · · · · · ·	are withdrawn from consideration.				
	laim(s) is/are allowed.					
	laim(s) <u>1-10,14-20,22-23 and 26-</u>	<u>29</u> is/are rejected.				
	laim(s) is/are objected to.	inting and/or algorithm and crimers and				
8) <u> </u>	laim(s) are subject to restri	ction and/or election requirement.				
Application	n Papers		•			
· · · · · · · · · · · · · · · · · · ·	ne specification is objected to by the					
•	*	e: a) ☐ accepted or b) ☐ objected to by				
		ection to the drawing(s) be held in abeyand	• •			
	· · · · · · · · · · · · · · · · · · ·	g the correction is required if the drawing(s to by the Examiner. Note the attached (				
,	•	o by the Examiner. Note the attached	Office Action of form PTO-152.			
Priority un	der 35 U.S.C. § 119					
•	<del>-</del>	n for foreign priority under 35 U.S.C. § 1	119(a)-(d) or (f).			
,	All b) Some * c) None of:					
		documents have been received.				
		/ documents have been received in App	· · · · · · · · · · · · · · · · · · ·			
ა.	· ·	s of the priority documents have been re onal Bureau (PCT Rule 17.2(a)).	eceived in this National Stage			
* See		on for a list of the certified copies not re	eceived.			
Attachment(s	)					
	of References Cited (PTO-892)		mmary (PTO-413)			
	of Draftsperson's Patent Drawing Review ( tion Disclosure Statement(s) (PTO/SB/08) lo(s)/Mail Date		/Mail Date ormal Patent Application			

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1. The response of the applicant has been read and given careful consideration. Responses to the arguments of the applicant are presented after the first rejection to which they are directed. Rejection of the previous office action not repeated below are withdrawn based upon the arguments of the applicant and the amendments to the claims.

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- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 3. Claims 1-10,14-20,22-23 and 26-29 are rejected under 35 U.S.C. 103(a) as being unpatentable over **either** Campbell, et al., "Fabrication of Photonic Crystals for the Visible Spectrum by Holographic Lithography, Nature, Vol. 404. pp. 53-56 (03/2000) **or** Turberfield, "Photonic Crystals made by Holographic Lithography, MRS Bull. Pp. 632-636 (08/2001), in view of Popovich et al. '152, Neckers et al. '802 and Oxman et al. WO99/62460

Campbell, et al., "Fabrication of Photonic Crystals for the Visible Spectrum by

Holographic Lithography, Nature, Vol. 404. pp. 53-56 (03/2000) teach the use of an Epoxy

based resist EPON SU8, with a triarylsulfonium salt as the photoinitiator/photoacid generator.

The resist is coated on a substrate, heated to remove the solvent, exposed to four beams.

"absorption of the UV photon by the molecule of PAG liberates a hydrogen ion; acid catalyzed polymerization occurs when the film is heated in a post-exposure bake". The photonic crystal structure is revealed by development using propylene glycol methylether acetate in an ultrasonic bath. (page 54). The formation of full connected polymer and air void lattices is disclosed. The filling of the resultant structure with titania is disclosed. (page 54, right column).

Turberfield, "Photonic Crystals made by Holographic Lithography, MRS Bull. Pp. 632-636 (08/2001) teaches the use of an Epoxy based resist EPON SU8, with a triarylsulfonium salt as the photoinitiator/photoacid generator. The resist is coated on a substrate, heated to remove the solvent, exposed to four beams. "absorption of the UV photon by the molecule of PAG liberates a hydrogen ion; acid catalyzed polymerization occurs when the film is heated in a post-exposure bake". The photonic crystal structure is revealed by development using propylene glycol methylether acetate in an ultrasonic bath. (page 633, right column). The formation of full connected polymer and air void lattices is disclosed. (page 634, center column). The filling of the resultant structure with titania is disclosed. (page 635, left column). The use of three beam exposure is disclosed. (page 625, left column).

Popovich et al. '152 teach the use of eosin and triethanol amine, fluorescein and triethanolamine, erythrosin B and triethanol amine systems as initiation systems extending spectral response of photopolymerizable systems into the 400 – 700 nm range. (These are all xanthene dyes, see prepub of the instant specification at [0040] and figures 4a-c)) The use of triethylamine and other amines as co-initiators is disclosed. (8/35-9/6). The formation of gratings using 488 nm lasers is disclosed.

Neckers et al. '802 in example 1 which comprises cyclohexene oxide (an epoxy), ethyl erythrosine (a xanthene dye), diaryliodonium hexafluoroantimonate and pentamethylaniline. When exposed to visible light 10 minutes are required for curing. Amines useful as coinitiators with onium salts are disclosed. (10/47-11/18). The use of these with novolak/Novolac resins is disclosed. (11/49-65).

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Oxman et al. WO99/62460 in examples 1-21 teach a mixture of acrylates and epoxy curable materials, together with diaryliodonium hexafluoroantimonate, camphorquinone, polytetrahydrofuran together with 22 different cationic polymerization modifiers. Example 5 uses 2,4,6-pentamethylaniline, example 6 used dimethylbenzylamine, example 13 used ethanolamine and example 10 uses triethylamine and the induction periods (the difference between T<sub>3</sub> and T<sub>2</sub> (control)) were determined. (page 25-30). For examples 5,6,10 and 13, the induction period raged from 0.51-3.46 minutes depending upon the amount and polymerization modifier used. (table 1 on page 29). The exposure was in the 400-500 nm range (22/22-26). Useful sensitizers include xanthene dyes (page 12/lines 1-13). Of the cationic polymerization modifiers listed on page 10, methyldimethanolamine, dibutylamine, diethanol amine, ethylemorpholine, (methylamino)ethanol and dimethylbenzylamine also increase the rate of polymerization once it begins.

It would have been obvious to one skilled in the art to modify the compositions and processes of either Campbell, et al., "Fabrication of Photonic Crystals for the Visible Spectrum by Holographic Lithography, Nature, Vol. 404. pp. 53-56 (03/2000) or Turberfield, "Photonic Crystals made by Holographic Lithography, MRS Bull. Pp. 632-636 (08/2001) which use sulfonium salts by using dye/onium together with amine coinitators/polymerization modifiers to extend the spectral response of these compositions and control the rate and onset of polymerization as disclosed by Neckers et al. '802 and Oxman et al. WO99/62460 and to use a longer wavelength laser, such as the 488 nm output of an argon ion laser to perform the interferometric exposure as taught by Popovich et al. '152, which ahs the benefit of the laser beams being visible to the eye, which allows easy adjustment of the laser beams.

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The applicant argues that the secondary references do not teach neutralizer molecules, but failed to assert this with respect to the rejections based upon the references made under 35 USC 102. The examiner also notes that the discussion of the secondary references clearly describe triethylamine and pentamethylaniline as useful coinitiators for onium salts. As these are bases, their neutralization of a certain amount of any photoacid generated is chemically inherent. The examiner points out that these are the same compounds discussed in the prepub of the instant specification at [0057]. The motivation is different from the reasons asserted by the applicant, as the references use the recited amines as co-initiators, but the induction effect is recognized in the art as evidenced by Oxman et al. WO99/62460. The increase in the speed of initiation once it has begun clearly translated to an increase in photospeed. The rejection stands. Also these couple well with the xanthene dyes to extend the spectral response of the composition.

In response to applicant's argument that the examiner's conclusion of obviousness is based upon improper hindsight reasoning, it must be recognized that any judgment on obviousness is in a sense necessarily a reconstruction based upon hindsight reasoning. But so long as it takes into account only knowledge which was within the level of ordinary skill at the time the claimed invention was made, and does not include knowledge gleaned only from the applicant's disclosure, such a reconstruction is proper. See *In re McLaughlin*, 443 F.2d 1392, 170 USPQ 209 (CCPA 1971). Further, there are clearly articulated benefits to adding the amines, particularly as coinitiators with onium salts as disclosed by Popovich et al. '152, Neckers et al. '802 and Oxman et al. WO99/6246 to increase the rate of polymerization and to increase the spectral sensitivity of the compositions when paired with xanthene dyes as disclosed in Popovich et al. '152. Further, the applicant's effect, the delay in the onset of polymerization,

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is already known in the art as evidenced by the teachings of Oxman et al. WO99/62460 with respect to induction periods and the 10 minute lag in curing observed by Neckers et al. '802.

The examiner notes that the heating step after exposure is already in the process of Campbell, et al., "Fabrication of Photonic Crystals for the Visible Spectrum by Holographic Lithography, Nature, Vol. 404. pp. 53-56 (03/2000) and Turberfield, "Photonic Crystals made by Holographic Lithography, MRS Bull. Pp. 632-636 (08/2001), so no modification of the processes of these references is required by the addition of the amines. The use of 488 nm lasers to form gratings is taught by Popovich et al. '152 as is the extension of spectral response into the 400-700 nm range from the UV (355 nm), so there is motivation for the extension of spectral response. The applicant apparently fails to appreciate the teaching that the while the induction period is increased by the addition of the amine co-initators, the reaction takes place faster after this point and that the induction period can be varied as taught in Oxman et al. WO99/62460 and while in an example of Neckers et al. '802 a 10 minute exposure is used, he is not making a grating and the intensity can be increased to shorten the exposure time. The examiner notes that the heating takes place after the exposure in Campbell, et al., "Fabrication of Photonic Crystals for the Visible Spectrum by Holographic Lithography, Nature, Vol. 404. pp. 53-56 (03/2000) or Turberfield, "Photonic Crystals made by Holographic Lithography, MRS Bull. Pp. 632-636 (08/2001), not concurrently. There is no need to draw out the exposure and the increase in the spectral sensitivity can be used to decrease the exposure. (Note that exposure is intensity multiplied by time). The applicant may realize a benefit for a particular composition containing a particular amount of the neutralizer, but no claims include these limitations and there is no

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comparative data in the record to support any such assertion. The applicant is invited to show the criticality of the amount of neutralizer in a proper declaration. The rejection stands.

4. Claims 1-10,14-20,22-23 and 26-29 are rejected under 35 U.S.C. 103(a) as being unpatentable over **either** Campbell, et al., "Fabrication of Photonic Crystals for the Visible Spectrum by Holographic Lithography, Nature, Vol. 404. pp. 53-56 (03/2000) **or** Turberfield, "Photonic Crystals made by Holographic Lithography, MRS Bull. Pp. 632-636 (08/2001), in view of Popovich et al. '152, Neckers et al. '802 and Oxman et al. WO99/62460, further in view of Cowan et al. '571.

Cowan et al. '571 teach the use of argon ion lasers and HeCd lasers (458 and 442) when forming crossed grating patterns to form 2D arrays of features.

In addition to the basis provided above, the examiner cites Cowan et al. '517 to support the position that the use of visible lasers in place of the UV lasers used in the exposure processes of either Campbell, et al., "Fabrication of Photonic Crystals for the Visible Spectrum by Holographic Lithography, Nature, Vol. 404. pp. 53-56 (03/2000) or Turberfield, "Photonic Crystals made by Holographic Lithography, MRS Bull. Pp. 632-636 (08/2001) as modified by of Popovich et al. '152, Neckers et al. '802 and Oxman et al. WO99/62460 would have been obvious and furthermore the use of visible lasers to expose resists twice to form arrays of features is old and well known in the holographic arts.

The rejection stands for the reasons above without further comment.

5. THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

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A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Martin J. Angebranndt whose telephone number is 571-272-1378.

The examiner can normally be reached on Monday-Thursday and alternate Fridays.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark Huff can be reached on 571-272-1385. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Martin J Angebranndt Primary Examiner Art Unit 1756

06/15/2006